

*“Rotating cylindrical magnetron sputtering: simulation of the reactive process”*. Depla D, Li XY, Mahieu S, van Aeken K, Leroy WP, Haemers J, de Gryse R, Bogaerts A, Journal of applied physics **107**, 113307 (2010). <http://doi.org/10.1063/1.3415550>